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This listing presents the papers in alphabetical order of the first author, subdivided according to the groupings "Solids and Materials" and "Surfaces, Interfaces, and Layer Structures". The author index that follows covers APPLIED PHYSICS A and B, and is presented in tabular form. The names are listed in alphabetical order in the first column. The second column the bibliographic data necessary to locate the paper. The issue is specified by the number separated from the volume number by a slash. The fourth column states the major PACS number so that the topic of the paper can be inferred by consulting the PACS listing on the left page.

SOLIDS and MATERIALS

Ahmad M., Zihlif A.:

Effect of mechanical tension on electrical transport properties of amorphous Fe92Zr8 alloy. Appl. Phys. A 45/3, 203-205 (1988) PACS: 72.15

Barringer E.A., Bowen H.K.:

Effects of particle packing on the sintered microstructure. Appl. Phys. A 45/4, 271-275 (1988) PACS: 81.20E 81.20

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Amorphous silicon logic integrated circuits.

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Phase transformation in a glass-ceramic observed by laser spectroscopy. Appl. Phys. A 45/3, 185-187 (1988) PACS: 61.40 66.30 78.00

Grader G.S., Gallagher P.K., Thomson J., Gurvitch M.: Rates of change in high temperature electrical resistivity and oxygen

diffusion coefficient in Ba2YCu3Ox. Appl. Phys. A 45/3, 179-183 (1988) PACS: 74.00 66.30 82.20

Ito Y., Takano T., Hasegawa M.:

Positron annihilation in synthetic zeolites. Comparison between lifetime and angular correlation data.

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A systematic analysis of defects in ion-implanted silicon. Appl. Phys. A 45/1, 1-34 (1988) PACS: 61.80 81.40 Leo K., Rühle W.W., Queisser H.J., Ploog K.:

Hot carrier cooling in GaAs quantum wells.

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Dose effects in ion implanted compound semiconductors. Appl. Phys. A 45/2, 113-118 (1988) PACS: 61.80 61.70

McElfresh M.W., Maple M.B., Yank K.N., Fisk Z .:

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Equilibrium dangling bond densities in a-Si:H and its related thin film

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Paprocki K., Brylowska I., Syszko W.:

Depth distributions of Au recoil atoms in silicon.

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High-Tc superconductivity in the multi phases Sr-Bi-Ca-Cu-O.

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Sharma S.K., Banerjee S., Kuldeep, Jain A.K.: Diffusion of Au and Cu in amorphous Fe80B20 and Fe82B18 alloys Appl. Phys. A 45/3, 217-220 (1988) PACS: 66.30 61.40

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Initial steps in the photochemical vapour deposition of amorphous

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Influence of laser fluence and the dopant gas pressure on the properties of photochemical doping of Si into GaAs using XeCl excimer

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Blocking of silicon oxidation by low-dose nitrogen implantation. Appl. Phys. A 45/1, 73-76 (1988) PACS: 68.55 73.40 73.20

Srinivasan R., Braren B.:

Ultraviolet laser ablation and etching of polymethyl methacrylate sensitized with an organic dopant.

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